

ABSTRACT

CONDUCTIVE FILM, METHOD FOR PRODUCING SAME, AND SPUTTERING
TARGET USED FOR SAME

Provided are a conductive film exhibiting low resistance, high reflectivity characteristics, and small surface roughness and having both high sulfuration resistance and heat resistance; a method for producing the conductive film; and a sputtering target used for the conductive film. The conductive film consists of a silver alloy having a component composition containing 0.1 to 1.5 at% of at least one of In and Sn and further containing 0.1 to 3.5 at% of Sb with the balance composed of Ag and unavoidable impurities. The conductive film is suitably used for a reflective electrode film for OLED elements in which a transparent conductive film for an OLED element is laminated on the surface of the conductive film and an electroluminescent layer including an organic EL layer is further laminated on the transparent conductive film.

[Selected Figure] FIG. 1